

ABSTRACT

A pattern comparison inspection apparatus comprises:
a reference position selecting portion (41) which selects
5 from among positions on an inspection target pattern a
reference position which is judged whether it should be
contained in an inspection region; an image comparing
portion (42) which compares an image signal at the
reference position with an image signal at a position
10 located an integral multiple of a repeat pitch away from
the reference position; and an inspection region setting
portion (43) which sets the inspection region by
containing therein the reference position when a
comparison result from the image comparing portion shows
15 a value not greater than a prescribed threshold value.
Thus, in the pattern comparison inspection apparatus
which performs inspection for a pattern defect by
comparing repeated patterns with each other in the
inspection target pattern having a repeated pattern
20 region, the inspection region can be enlarged within the
bounds of the repeated pattern region.